

13 3 a liquid recycling system in fluid communication with the non-thermal plasma reactor.

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REMARKS

Claims 57 and 70 have been amended for purposes of clarification. Support for the amendment to claim 57 is found in the specification at page 15, lines 1-6 and page 18, lines 3-5. Support for the amendment to claim 70 is found in the specification at page 24, line 8 – page 25, line 22 and FIG. 5. Claims 88-95 have been added. Support for claim 88, 91 and 92 is found throughout the specification, particularly at page 7, lines 26-27. Support for claim 89 is found in the specification at page 7, lines 20-23 and page 10, lines 22-23. Support for claim 90 is found in the specification at page 10, lines 22-23. Support for claim 93 and 94 is found throughout the specification, particularly at page 15, line 18 – page 19, line 14 and FIG. 1. Support for claim 95 is found in the specification at page 24, line 8 – page 25, line 22 and FIG. 5. Entry of these amendments is respectfully requested.

Respectfully submitted,

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**Marked-up Version of Amended Claims
Pursuant to 37 C.F.R. §§ 1.121(b)-(c)**

The claims have been amended as follows:

57. (Amended) A process for treating a halogen-containing gas, comprising:
providing a chamber defining at least one gas inlet for receiving a feed gas mixture that includes a halogen-containing gas and a gaseous reducing agent, and at least one water inlet for receiving liquid water;

providing at least one first electrode disposed within the chamber;

providing at least one second electrode disposed within the chamber;

flowing the liquid water over at least a portion of the first electrode; and

applying electric potential to at least one of the first [and] or second electrodes so as to generate a plasma in the feed gas mixture and reduce the halogen-containing gas.

70. (Amended) A system for treating fluorine gas, comprising:

a non-thermal plasma reactor for converting fluorine gas to hydrogen fluoride;

a fluorine gas source in fluid communication with the non-thermal plasma reactor;

[a hydrogen gas source in fluid communication with the non-thermal plasma reactor;] and

a liquid water source in fluid communication with the non-thermal plasma reactor.